

ESSDERC 89

Springer-Verlag - Sidewall Contact for npn/pnp Transistors by Selective Oxidation (SELOX)



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- Solid state electronics -- Congresses.ESSDERC 89

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Guido Masetti — University of Bologna — Publications

Mallik, Kanad, de Groot, C.

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Due to this, rectification was present in these mol. We believe that our theoretical exploration provides key insights into the transport behavior of this molecule which will inevitably aid device design for molecular electronic device applications.

Self

Dry Oxidation of Silicon: A New Model of Growth Including Relaxation of Stress by Viscous Flow. Subramanian 197th Meeting of The Electrochemical Society, Toronto, May 14-18, 2000. Schrimpf, Sameer Pendharkar and Kaustav Banerjee Journal of Applied Physics, Vol.

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Workshop on VLSI Process and Device Technology VPAD , pp.

Literatur

Ionescu and Kaustav Banerjee Springer Kluwer , ISBN: 1-4020-7533-2, 622 pp. A comparison between the two counterion systems and configuration 1 is shown in.

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